

# IIT School Program - June 3-5, 2010

## Thursday June 3 (Seminar RoomII,III)

09:00 – 10:30	<b>History of Electronics</b>	<b>James Ziegler</b>
10:30 – 11:00	<b>(Break)</b>	
11:00 – 12:00	<b>Introduction to Ion Implantation</b>	<b>James Ziegler</b>
12:00 – 13:00	<b>(Lunch)</b>	
13:00 – 14:30	<b>Review of CMOS Devices</b>	<b>Leonard Rubin</b>
14:30 – 15:00	<b>(Break)</b>	
15:00 – 17:00	<b>The Problems of Shallow Junctions</b>	<b>Michael Current</b>
17:15 – 19:00	<b>(Reception*)</b>	

## Friday June 4 (Science) (Seminar RoomII)

09:00 – 10:00	<b>Ion Implantation Damage</b>	<b>Kevin S. Jones</b>
10:00 – 10:30	<b>(Break)</b>	
10:30 – 12:00	<b>Ion Implantation Annealing</b>	<b>Kevin S. Jones</b>
12:00 – 13:00	<b>(Lunch)</b>	
13:00 – 14:30	<b>Cluster Ion Beam Implantation</b>	<b>Isao Yamada</b>
14:30 – 15:00	<b>(Break)</b>	
15:00 – 16:30	<b>Plasma Immersion Ion Implantation</b>	<b>Susan Felch</b>

## Friday June 4 (Technology) (Seminar RoomIII)

09:00 – 10:00	<b>Implanter Concepts</b>	<b>David Chivers</b>
10:00 – 10:30	<b>(Break)</b>	
10:30 – 12:00	<b>Ion Sources – Concepts</b>	<b>Anthony Renau</b>
12:00 – 13:00	<b>(Lunch)</b>	
13:00 – 14:00	<b>Ion Sources – Repair and Maintenance</b>	<b>Anthony Renau</b>
14:00 – 14:30	<b>(Break)</b>	
14:30 – 15:30	<b>End-Station Problems</b>	<b>T. C. Smith</b>
15:30 – 17:30	<b>Implanter Safety</b>	<b>Stephen Roberge</b>

## Saturday June 5 (Seminar RoomII,III)

09:00 – 10:00	<b>Future of CMOS on SOI</b>	<b>Devendra Sadana</b>
10:00 – 10:30	<b>(Break)</b>	
10:30 – 11:30	<b>New CMOS Devices and Future Manufacturing Processes</b>	<b>Devendra Sadana</b>
11:30 – 12:30	<b>Variability Issues and The New Possibility of Ion Implantation</b>	<b>Tohru Mogami</b>

\* Reception is free. Light food & beer will be served.